Q. Metrology, Inspection, Analysis, and Yield Enhancement 분과

2021년 1월 29일(금), 10:45–12:15 / 채널 A

[FA2-Q] Metrology, Inspection, and Yield Enhancement I

좌장: 정용우 박사 (SK하이닉스), 조용재 박사 (KRISS)

Session	Presentation
FA2-Q-1 **10:45-11:15**	[초청] **Digital X-ray Sources based on Carbon Nanotube Field Emitters for Semiconductor Inspections** Yoon-Ho Song *Materials and Components Division, ICT Creative Research Laboratory, ETRI*
FA2-Q-2 **11:15-11:45**	[초청] **Real-time Monitoring of Contamination Particles in Semiconductor Process** Jihun Mun[1], and Sang-Woo Kang[1,2] *[1]Advanced Instrumentation Institute, KRISS, [2]Science of Measurement, UST*
FA2-Q-3 **11:45-12:00**	**A Hybrid Metrology & Inspection Solution for Semiconductor Manufacturing Process** Wookrae Kim, Gwangsik Park, Changhyeong Yoon, Jinseob Kim, Daehoon Han, Jaehwang Jung, and Myungjun Lee *MI Equipment R&D Team, Mechatronics R&D Center, Samsung Electronics Co., Ltd.*
FA2-Q-4 **12:00-12:15**	**An Instance Selection Algorithm under the Unsupervised Condition for a Virtual Metrology of Critical Dimension in Semiconductors** In Seok Park[1], JunHui Lee[1], Min Su Kim[1], Wan Sik Nam[2], Heeyoon Han[2], Sooseok Lee[2], Chihoon Lee[2], and PooGyeon Park[1] *[1]Department of Electrical Engineering, POSTECH,* *[2]Measurement & Inspection Team, Memory Business, Samsung Electronics Co., Ltd.*